

### **Amendments to the Claims:**

This listing of claims will replace all prior versions and listings of claims in the application.

### **Listing of Claims:**

1. (currently amended): A liquid injection module for a vapor liquid delivery system, said liquid injection module comprising:

a liquid injector, ~~said liquid injector is used to inject~~ injecting a liquid source and ~~make making~~ said liquid source atomized to be an atomized liquid source;

a purging gas provider, ~~said purging gas provider is used to provide~~ providing a purging gas to purge out said liquid source that remains inside said liquid injector;

a first three-way valve, ~~said first three-way valve is used to connect~~ located between said liquid source, said purging gas provider and said liquid injector; and

an exhausting branch, ~~said exhausting branch disposes~~ adjacent said liquid injector, and said exhausting branch ~~is used to exhaust~~ exhausting redundant said liquid source that is purged by a purging gas.

2. (currently amended): The liquid injection module according to claim 1, wherein said purging gas is selected from the group consisting of N<sub>2</sub> (nitrogen), CO<sub>2</sub>, Ar and He.

3. (currently amended): The liquid injection module according to claim 1, further comprising a carrier gas, ~~said carrier gas is used to carry~~ carrying said atomized liquid source.

4. (currently amended): The liquid injection module according to claim 3, wherein said ~~carrier gas~~ liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane[[]]); C<sub>4</sub>H<sub>16</sub>O<sub>4</sub>Si<sub>4</sub>).

5. (currently amended): The liquid injection module according to claim 1, further comprising a second three-way valve, wherein said second three-way valve ~~connect~~ connects said exhausting branch, a gas line, and a delivery line, and said gas line ~~depositing~~ located between said liquid injector and said second three-way valve, and said second three-way valve is used to control flow between said exhausting branch and said liquid injector.

6. (currently amended): The liquid injection module according to claim 5, further comprising a carrier gas provider, ~~said carrier gas provider is used to provide~~ providing a carrier gas to carry said atomized liquid source.

7. (cancelled)

8. (currently amended): A heating injection apparatus for a vapor liquid delivery system used in a chemical vapor deposition (CVD) process, said heating injection apparatus comprising:

a liquid injector, ~~said liquid injector is used to inject~~ injecting a liquid source, and ~~make~~ making said liquid source atomized to be an atomized liquid source while said liquid source injecting;

a purging gas provider, ~~said purging gas provider is used to provide~~ providing a purge purging gas to purge out said liquid source that remains inside said liquid injector;

a first three-way valve, ~~said first three-way valve is used to connect~~ located between said liquid source, said purging gas provider, and said liquid injector;

an exhausting branch, ~~said exhausting branch disposes~~ disposed adjacent said liquid injector, and said exhausting branch ~~is used to exhaust~~ exhausting redundant said liquid source that is purged by said purging gas; and

a heating means for heating gases, said heating means depositing located between said liquid injector and a carrier gas provider, said carrier gas provider ~~is used to provide~~ providing a carrier gas to carry said atomized liquid source.

9. (currently amended): The heating ~~liquid~~ injection apparatus according to claim 8, wherein said purging gas is selected from the group consisting of N<sub>2</sub> (nitrogen), CO<sub>2</sub>, Ar and He.

10. (currently amended): The heating ~~liquid~~ injection apparatus according to claim 8, wherein said heating means ~~for heating gases~~ is a thermostat device, and ~~the heating source of~~ wherein said thermostat device is selected from the ~~device group~~ consisting of a heating coil and an infrared ray thermostat device.

11. (currently amended): The heating ~~liquid~~ injection apparatus according to claim 10, wherein said thermostat device is used to heat said carrier gas.

12. (currently amended): The heating ~~liquid~~ injection apparatus according to claim 8, wherein said ~~carrier gas liquid source~~ is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane;  $C_4H_{16}O_4Si_4$ ).

13. (currently amended): The heating ~~liquid~~ injection apparatus according to claim 8, further comprising a second three-way valve, ~~wherein said second three-way valve connecting~~ said exhausting branch, a gas line, and a delivery line, and said gas line is a passageway that ~~deposited is~~ disposed between said liquid injector and said second three-way valve.

14. (currently amended): A heating ~~liquid~~ injection apparatus for a vapor liquid delivery system used in a chemical vapor deposition (CVD) process, said heating injection apparatus comprising:

a liquid injector, ~~said liquid injector is used to injecting~~ a liquid source and ~~make making~~ said liquid source ~~to become atomization atomized~~ to be an atomized liquid source while said liquid source injecting;

a purging gas provider, ~~said purging gas provider is used to provide providing~~ a purging gas to purge out said liquid source that remains inside said liquid injector;

a carrier gas provider, ~~said carrier gas provider is used to provide providing~~ a carrier gas to carry said atomized liquid source;

a first three-way valve, ~~said first three-way valve is used to connect located~~ between said liquid source, said purging gas provider and said liquid injector[.];

an exhausting branch, ~~said exhausting branch disposes disposed~~ adjacent said liquid injector, ~~and said exhausting branch is used to exhausting~~ redundant said liquid source that ~~been~~ is purged by said purging gas to prevent a polymerization around said liquid injector;

a second three-way valve, ~~said second three-way valve connecting~~ said exhausting branch, a gas line and a delivery line, said gas line is ~~the~~ a passage that ~~deposited is~~ located

between said liquid injector and said second three-way valve, and said second three-way valve is ~~used to control~~ controlling the flow between said exhausting branch and said liquid injector; and

a thermostat device ~~depositing~~ located between said liquid injector and said carrier gas provider, said thermostat device ~~is used to heating~~ said carrier gas, and said thermostat device is selected from the ~~device group~~ consisting of a heating coil and an infrared ray thermostat device.

15. (currently amended): The heating ~~liquid~~-injection apparatus according to claim 14, wherein said purging gas is selected from the group consisting of N<sub>2</sub> (nitrogen), CO<sub>2</sub>, Ar and He.

16. (currently amended): The heating ~~liquid~~-injection apparatus according to claim 14, wherein said ~~carrier gas~~ liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; ~~[[I]]~~ C<sub>4</sub>H<sub>16</sub>O<sub>4</sub>Si<sub>4</sub>).

17. (New): A method for a heat injection apparatus for a vapor liquid delivery system, said method comprising the steps of:

- providing a liquid source;
- purging out said liquid source remaining inside a liquid injector by a purging gas;
- atomizing said liquid source to be an atomized liquid source after the step of purging out;
- injecting said atomized liquid source into a gas line;
- exhausting said purging gas;
- providing a carrier gas;
- heating said carrier gas to the demanded production temperature before said carrier gas enters said gas line;
- carrying said atomized liquid source through a delivery line into a gas-mixing device by said carrier gas; and
- entering said atomized liquid source through a gas-mixing device into a reaction chamber to perform a deposition process.

18. (New): The method according to claim 17, wherein said liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; C<sub>4</sub>H<sub>16</sub>O<sub>4</sub>Si<sub>4</sub>).

19. (New): The method according to claim 17, wherein said purging gas is selected from the group consisting of N<sub>2</sub> (nitrogen), CO<sub>2</sub>, Ar and He.

20. (New): The method according to claim 17, wherein said carrier gas is He (helium).

21. (New): The method according to claim 17, wherein the step of heating the carrier gas comprises heating the carrier gas with a thermostat device that comprises a heating coil.

22. (New): The method according to claim 17, wherein the step of heating the carrier gas comprises heating the carrier gas with a thermostat device that comprises an infrared ray device.